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**APPENDICES**

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## APPENDIX A

### Mechanical properties

#### The temporary solder mask A

#### 1. Tensile Strength

**Table A.1** The tensile strength of solder mask with various NVP: HPMA monomer concentration

Amount of NVP: HPMA (phr)	Tensile strength (MPa)			
	Run #1	Run #2	Run #2	Average
30:20	3.05	3.32	3.38	3.25
25:25	3.67	3.45	3.53	3.55
20:30	3.71	3.68	3.62	3.67

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**Table A.2** The tensile strength of solder mask with various amount of UT-50 acrylic polymer

Amount of UT-50 (phr)	Tensile strength (MPa)			
	Run #1	Run #2	Run #2	Average
40	3.16	3.41	3.36	3.31
50	2.93	3.16	3.06	3.05
60	1.75	1.69	2.07	1.87
70	0.43	0.35	0.39	0.39

**Table A.3** The tensile strength of solder mask with various amount of pigment (TiO<sub>2</sub>)

Amount of TiO <sub>2</sub> (phr)	Tensile strength (MPa)			
	Run #1	Run #2	Run #2	Average
1	3.16	3.07	2.95	3.06
2	3.07	3.03	3.31	3.17
3	3.12	3.14	3.07	3.11
4	3.11	3.08	3.08	3.09

## 2. Elongation

**Table A.4** The elongation (%) of solder mask with various NVP: HPMA monomer concentration

Amount of NVP: HPMA (phr)	Elongation (%)			
	Run #1	Run #2	Run #2	Average
30:20	48.95	51.03	50.02	50.00
25:25	67.00	65.23	65.77	66.00
20:30	41.05	39.95	39.00	40.00

**Table A.5** The elongation (%) of solder mask with various amount of UT-50 acrylic polymer

Amount of UT-50 (phr)	Elongation (%)			
	Run #1	Run #2	Run #2	Average
40	110.18	118.32	120.13	116.21
50	196.71	197.22	193.14	195.69
60	391.30	390.60	401.30	394.40
70	527.01	540.98	537.01	535.00

**Table A.6** The elongation (%) of solder mask with various amount of pigment (TiO<sub>2</sub>)

Amount of TiO <sub>2</sub> (phr)	Elongation (%)			
	Run #1	Run #2	Run #2	Average
1	196.37	198.25	195.81	196.81
2	197.93	196.41	196.42	196.92
3	193.59	192.84	193.22	193.21
4	187.08	192.13	191.12	190.11

**The temporary solder mask B****Table A.7** The Effect of solder mask with various amount of polyvinyl alcohol

Properties	Amount of PVA (GH-17):PVA(GL-05) (phr)						
	5:5	5:10	5:15	5:20	10:5	15:5	20:5
Tensile strength (Mpa)	21.34	19.40	15.03	14.23	23.12	24.97	26.16
Elongation at break (%)	20.02	45.32	63.12	82.03	17.82	16.23	16.12
Adhesion	0B	0B	0B	0B	0B	0B	0B

**Table A.8** The effect of solder mask with various amount of HPMA: NVP monomer

Properties	Amount of HPMA: NVP (phr)					
	1:1	1:2	1:3	2:2	2:1	3:1
Tensile strength (Mpa)	19.57	18.32	18.17	23.21	21.96	25.10
Elongation at break (%)	45.76	47.54	39.13	47.32	47.35	30.02
Adhesion	0B	0B	0B	0B	0B	0B

### 3. Adhesion strength

3.1 Adhesion strength (ASTM D 816-82 : Standard Test methods for rubber cements)

**Table A.9** Adhesion strength of temporary solder masks with various amount of releasing agent (silicone oil 350s)

Amount of Silicone oil 350s (phr)	Adhesion strength (N)			
	Run #1	Run #2	Run #2	Average
0	209.47	219.80	220.98	216.75
2	153.56	153.92	150.20	152.56
5	132.13	124.86	125.09	127.36
10	105.70	102.00	110.30	106.00
15	72.00	70.46	70.48	70.98



**Table A.10** The Effect of releasing agent

Properties	Test methods	Amount of releasing agent (phr)				
		0	2	5	10	15
Adhesion	ASTM D3359-97	1B	1B	1B	1B	0B

#### 4. Viscosity of Temporary Solder Masks

**Table A.11** Viscosity of solder masks A with various amounts of thickening agent

(T-45)

Amount of T-45 (phr)	Viscosity (Cps)			
	Run #1	Run #2	Run #2	Average
2	63,200	63,900	64,000	63,700
5	66,300	66,100	65,900	66,100
10	74,400	74,700	74,700	74,600
15	80,000	80,300	80,000	80,100
20	83,150	83,080	83,070	83,100
25	94,400	94,650	94,750	94,600

**Table A.12** Viscosity of solder masks B with various amounts of thickening agent  
(xanthan gum)

<b>Amount of xanthan gum (g)</b>	<b>Viscosity (cps.)</b>
0.1	24,000
0.2	30,000
0.3	35,000
0.4	39,500
0.5	44,500

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## APPENDIX B

The glass transition temperature was determined by DSC method under the following condition.

Sample weight: 10-20 mg  
Container: aluminum pan  
Temperature: 0 – 300°C



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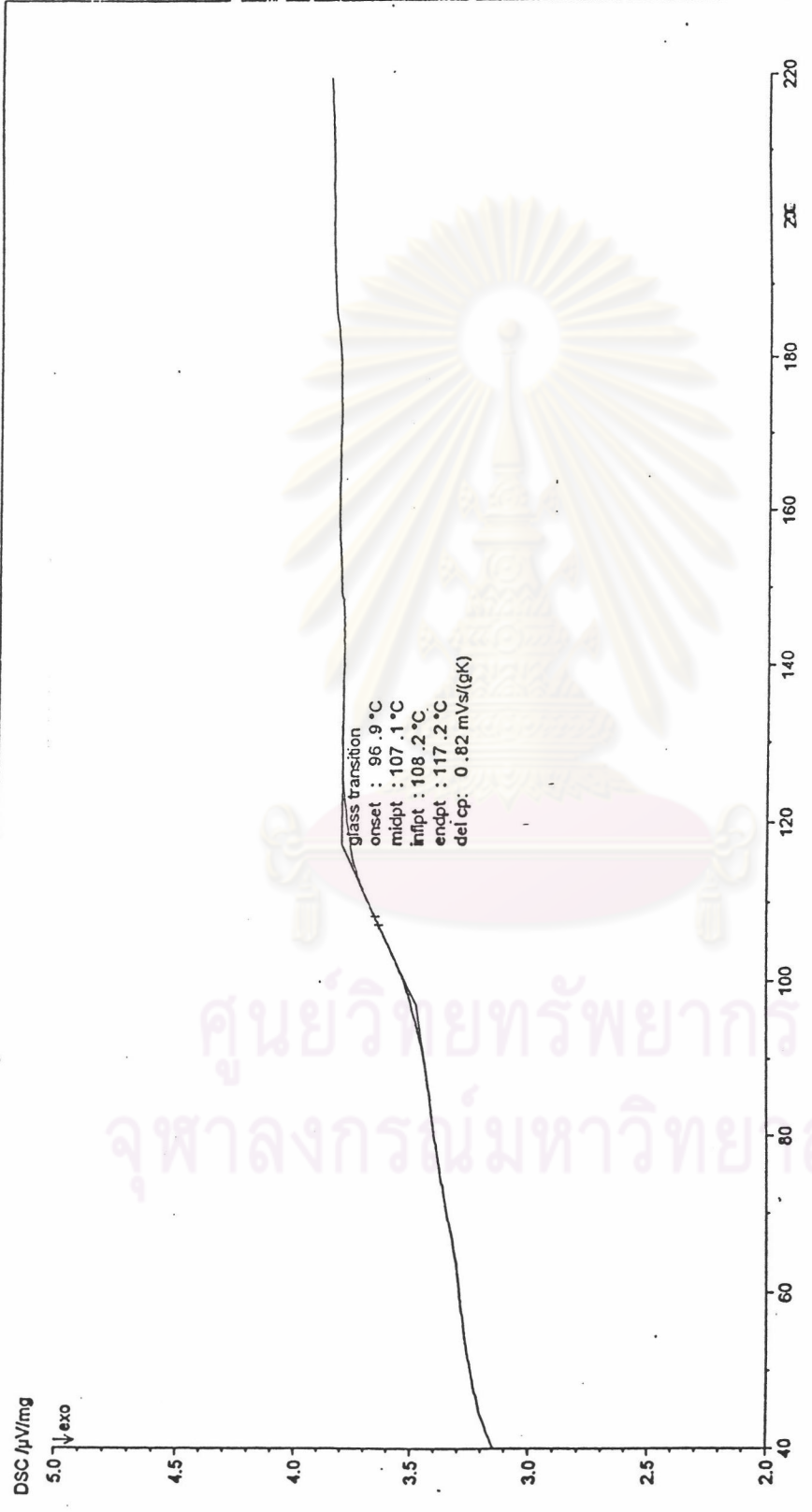


Figure B.1 DSC thermogram of temporary solder mask A



Figure B.2 DSC thermogram of temporary solder mask B

**APPENDIX C**

The thermal degradation property of the solder mask was obtained from thermogravimetric analysis (TGA) under the test conditions as shown below:

Sample Weight:	10 mg
Container:	Platinum pan
Temperature:	50-800°C
Heating-Cooling rate:	20°C/min
Purged-gas:	original air 30/15



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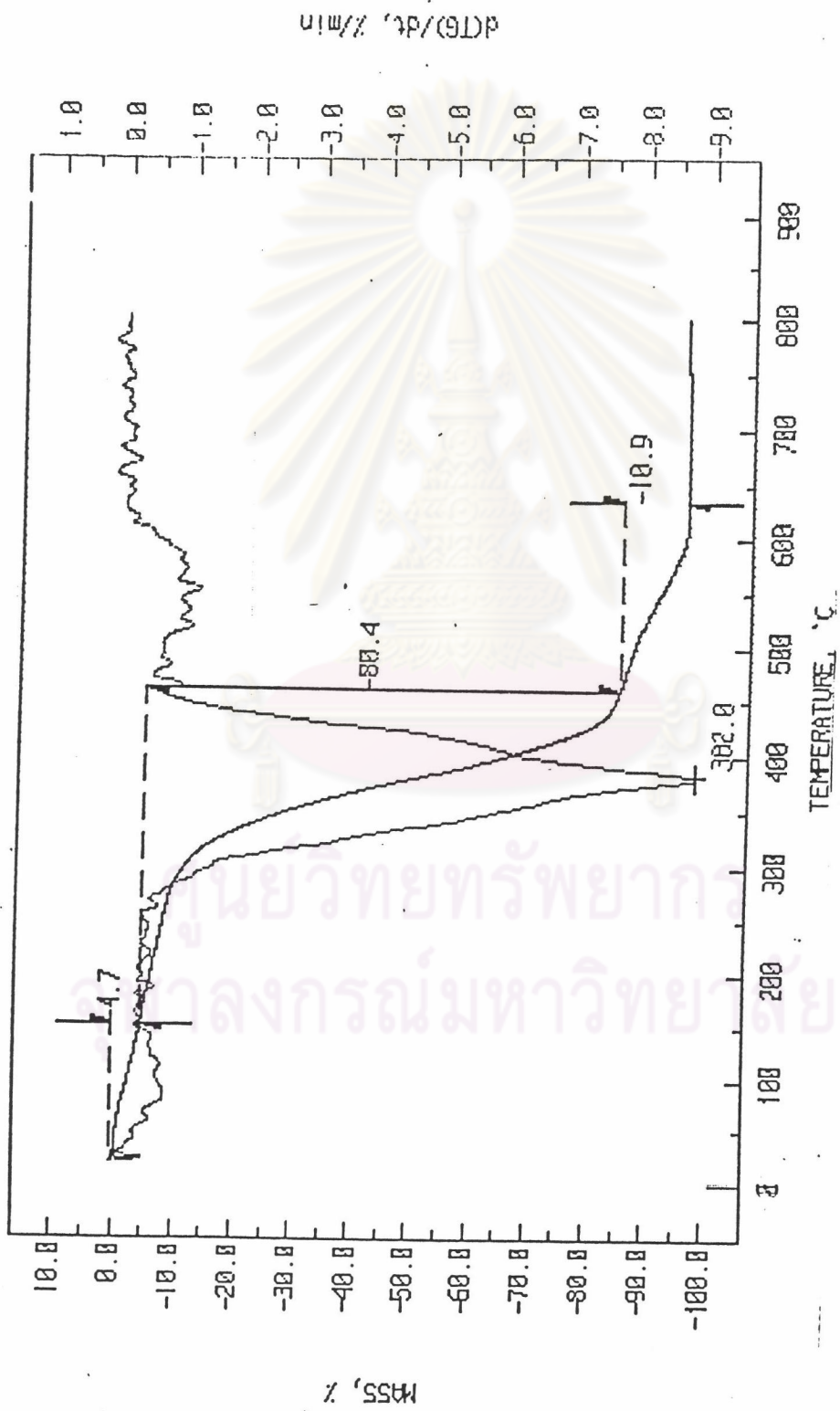


Figure C.1 TGA thermogram of temporary solder mask A before adding filler

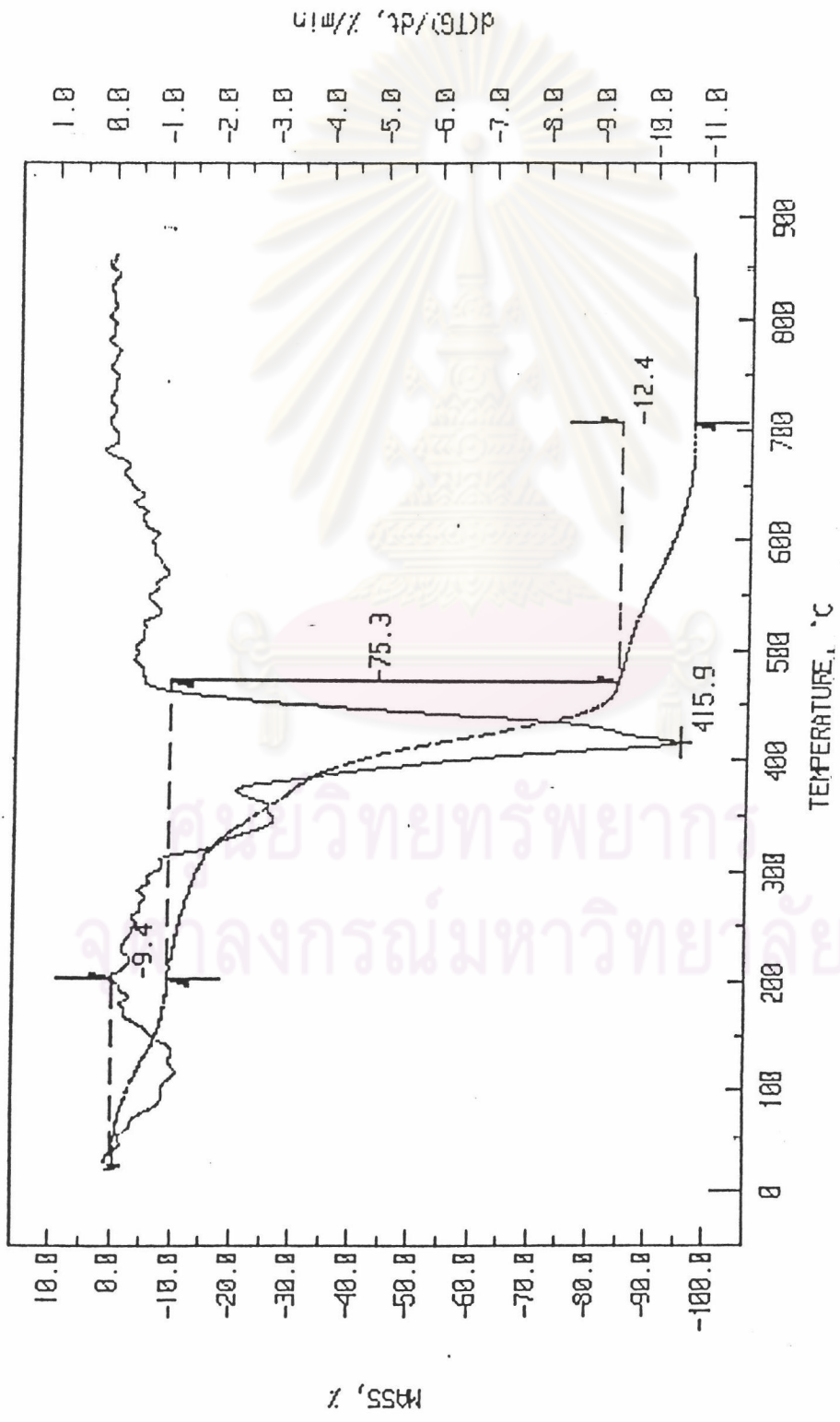


Figure C.2 TGA thermogram of temporary solder mask A after adding filler



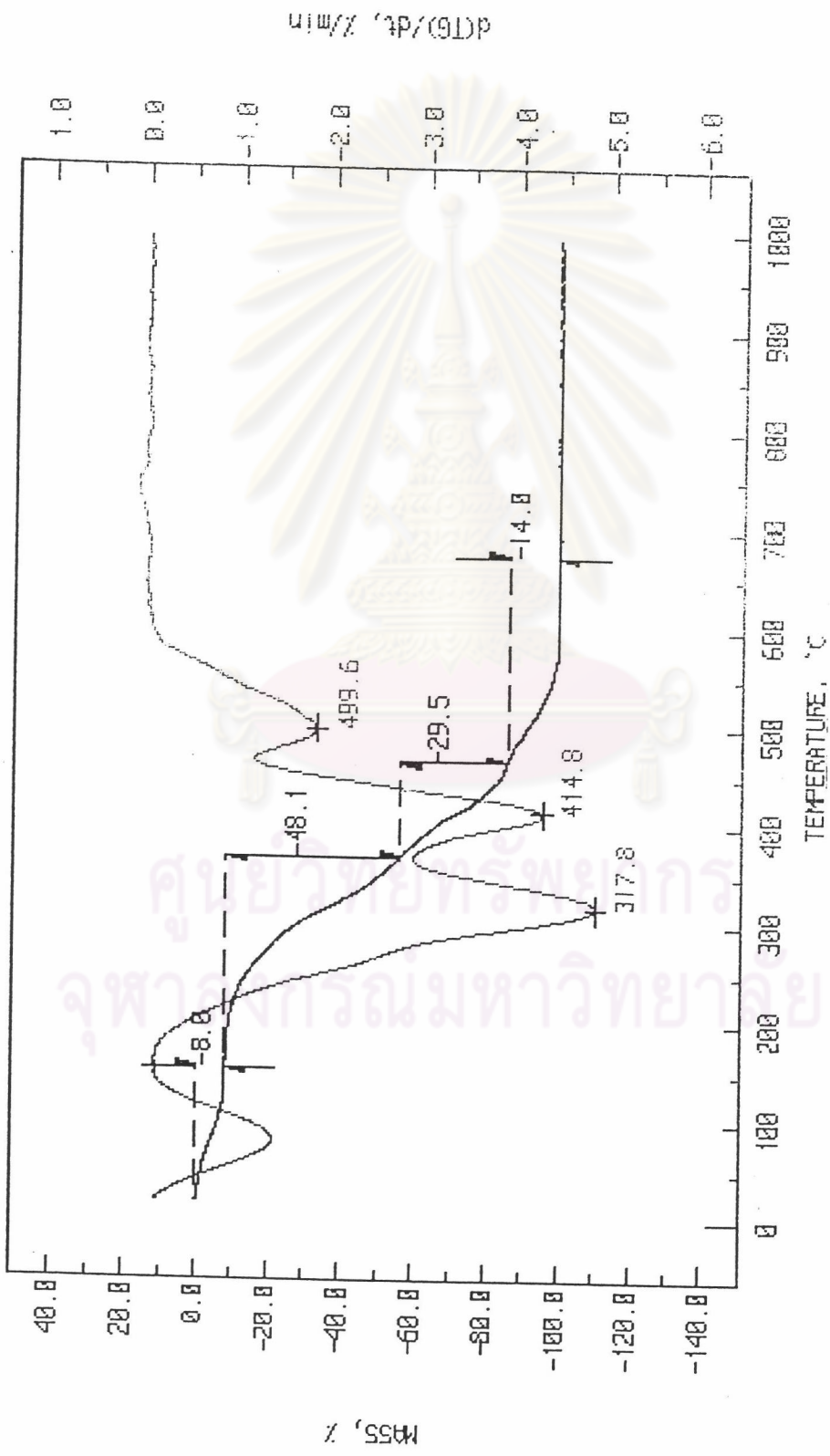


Figure C.3 TGA thermogram of temporary solder mask B

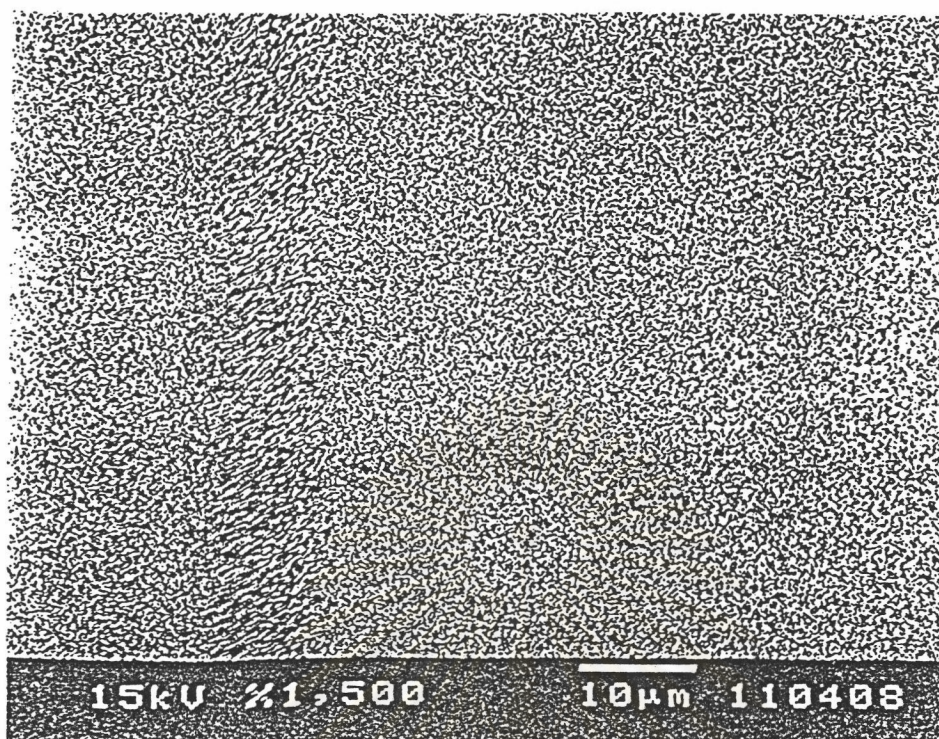
**APPENDIX D**

The characterization of the surface of the temporary solder mask was obtained from scanning electron microscopy (SEM) under the as shown below:

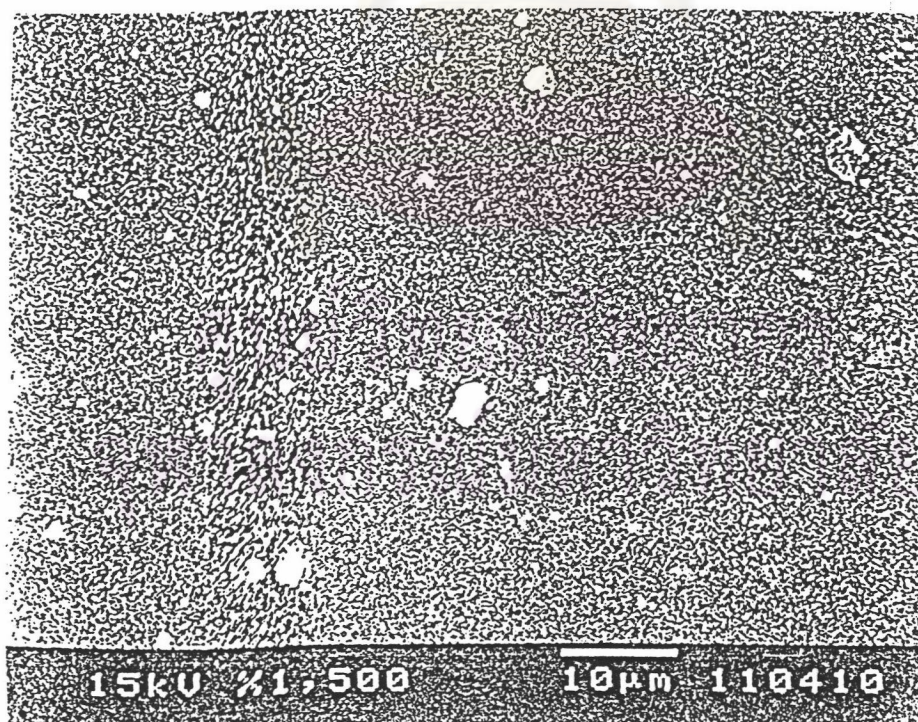
Sample weight	:	10-20 mg.
Container	:	aluminum pan
Temperature	:	50-150 °C



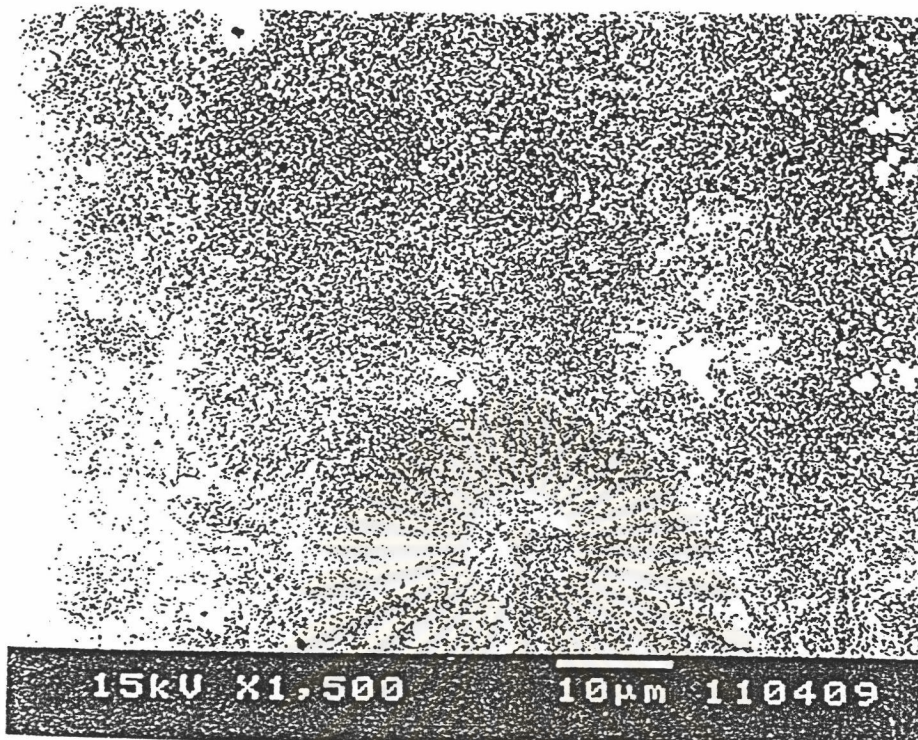
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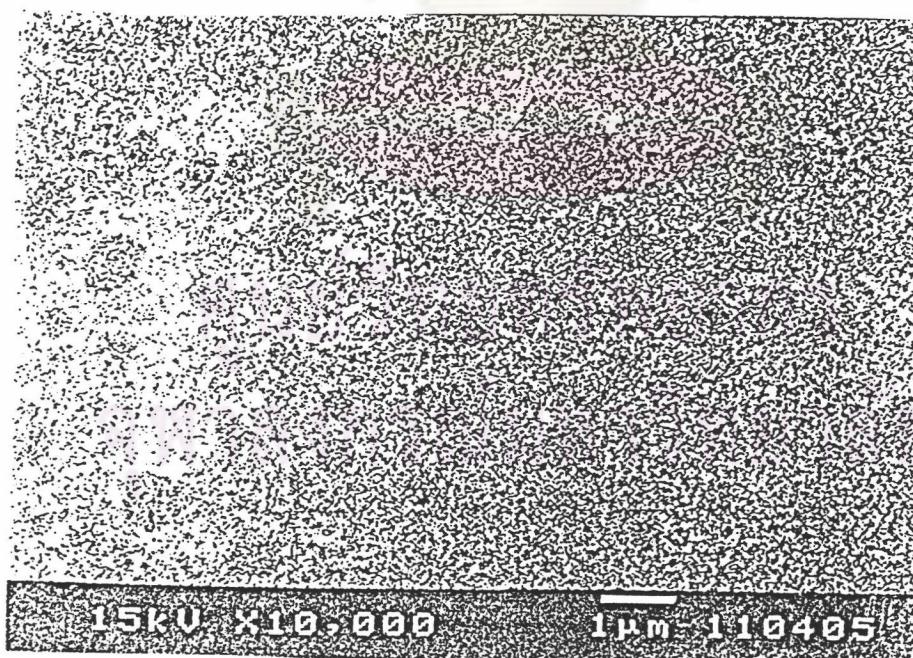
**Figure D.1** SEM photomicrograph of temporary solder mask No.1  
(1,500x magnification)



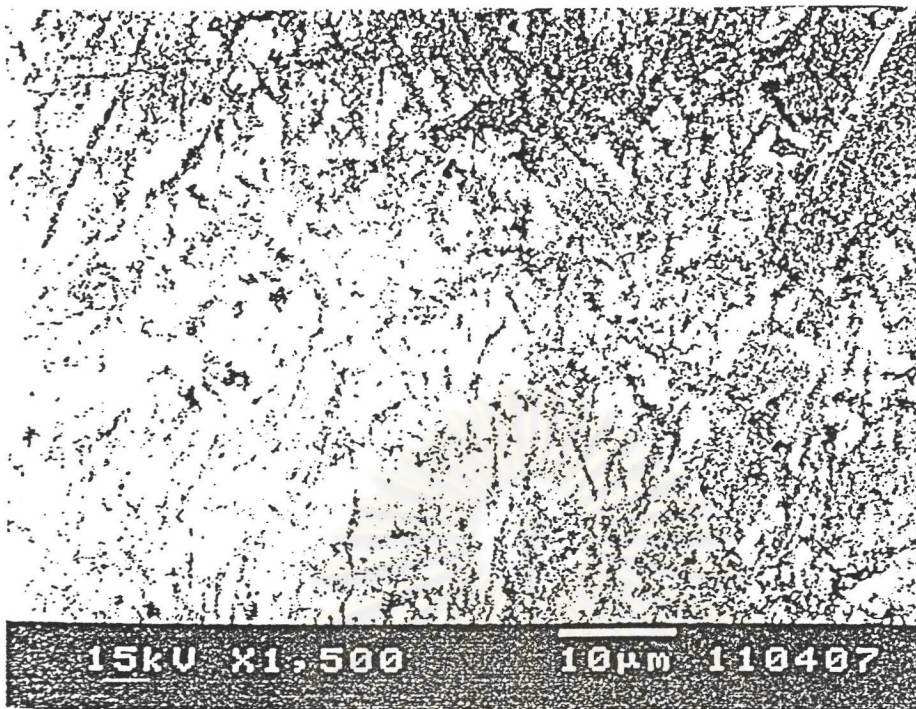
**Figure D.2** SEM photomicrograph of temporary solder mask No.2  
(10,000x magnification)



**Figure D.3** SEM photomicrograph of temporary solder mask No.3  
(1,500x magnification)



**Figure D.4** SEM photomicrograph of temporary solder mask No.4  
(1,500x magnification)

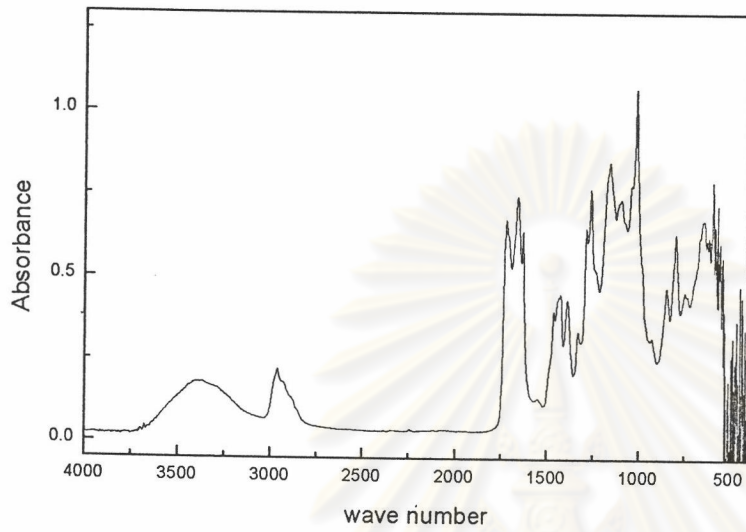


**Figure D.5** SEM photomicrograph of temporary solder mask No. 5  
(1,500x magnification)

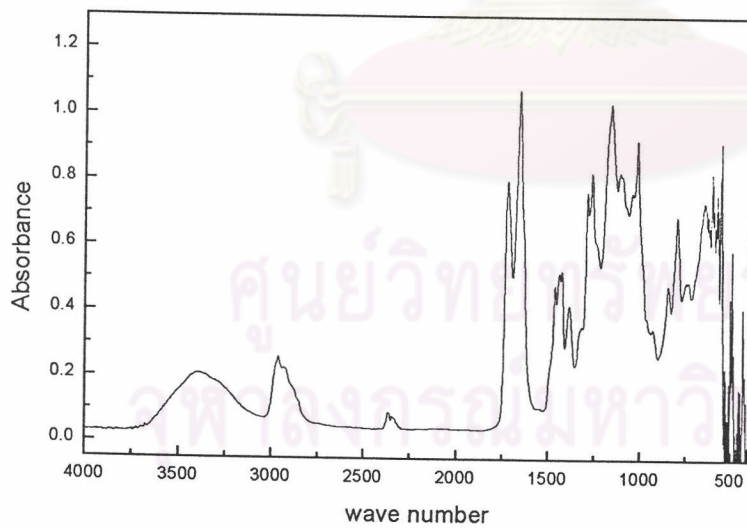
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## APPENDIX E

## ATR FT-IR Spectroscopy



**Figure E.1** The ATR FT-IR of ratio NVP:HPMA 30:20



**Figure E.2** The ATR FT-IR of ratio NVP:HPMA 25:25

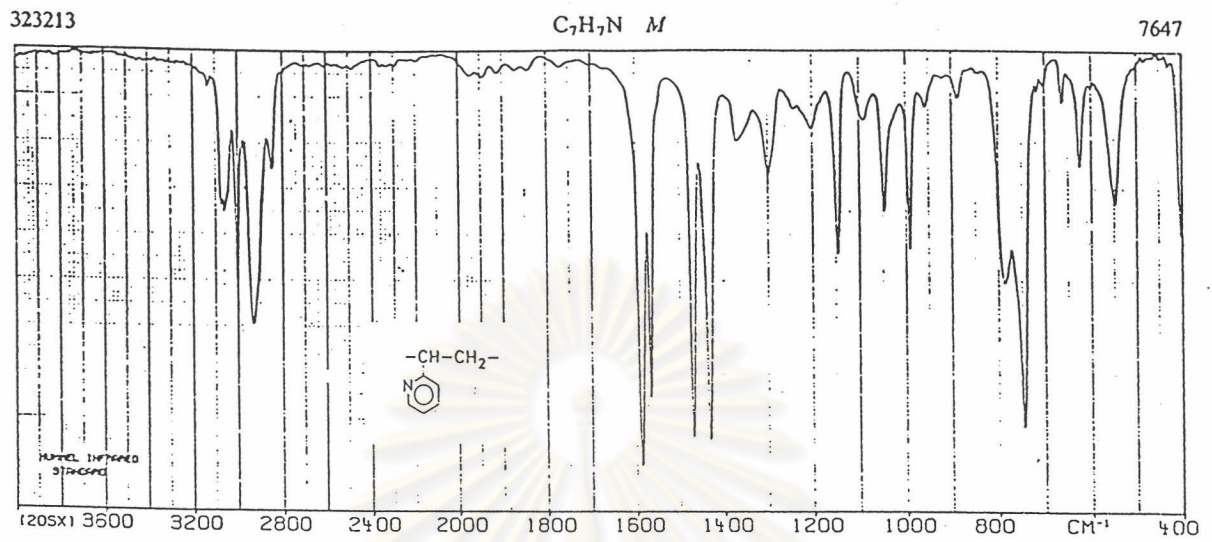


Figure E.3 The ATR FT-IR of poly(N-vinylpyrrolidone)

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## VITA

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